APPENDIX

VERSION SHOWING CHANGES MADE TO CLAIMS

1. (Amended) A laser oscillating apparatus that excites [for exciting] a laser gas by an electromagnetic wave and resonates [resonating] generated plasma light so as to generate laser light,

wherein a light emission portion for the [of said] plasma light is a slit-shaped gap formed along a lengthwise direction of a plate member [provided above and away from an electromagnetic-wave emission source].

2. (Amended) The laser oscillating apparatus according to claim 1, further comprising a shielding structure having a shielding wall covering said electromagnetic-wave emission source,

wherein said shielding structure is internally supplied with the [said] laser gas,

and wherein an upper surface of said shielding structure comprises [is used as] said plate member[, and said gap is formed along the lengthwise direction of said plate member].

3. (Amended) The laser oscillating apparatus according to claim 2, wherein said shielding structure comprises a pair of chambers communicating with each other via the [said] gap.

4. (Amended) The laser oscillating apparatus according to claim 3, wherein an [said] electromagnetic-wave emission source is provided in each of said chambers.

5. (Amended) The laser oscillating apparatus according to claim 1, wherein a waveguide comprising a pair of chambers internally supplied with laser gas is provided above and below said plate member, said pair of chambers in communication with each other via the [said] gap,

and wherein an [said] electromagnetic wave is generated in one of said pair of chambers and is propagated to the other one of said pair of chambers through the [said] gap, to continuously cause [said] plasma light over the entire area along the lengthwise direction where the [said] gap is formed.

6. (Amended) The laser oscillating apparatus according to claim 5, wherein an end of one of said pair of chambers is offset from [shifted to that of] the other one of said pair of chambers by a predetermined distance.

7. (Amended) The laser oscillating apparatus according to claim 21 [1], wherein an opening of said electromagnetic-wave emission source is wider than the [said] slit-shaped gap provided above the [said] opening.

8. (Amended) A laser oscillating apparatus that excites [for exciting] a laser gas by an electromagnetic wave and resonates [resonating] generated plasma light so as to generate laser light, comprising:

a waveguide [awaveguide] comprising a pair of chambers each internally supplied with [said] laser gas,

wherein said waveguide [saidwaveguide] has a slit-shaped gap in a lengthwise direction, and said pair of chambers communicate with each other via the [said] gap,

and wherein an [said] electromagnetic wave is generated in one of said pair of chambers and is propagated to the other one of said pair of chambers through the [said] gap, to continuously cause [said] plasma light over the entire area along the lengthwise direction where the [said] gap is formed.

9. (Amended) The laser oscillating apparatus according to claim 8, wherein an end of one of said pair of chambers is offset from [shifted to that of] the other one of said pair of chambers by a predetermined distance.

10. (Amended) The laser oscillating apparatus according to claim 1, wherein the [said] laser gas is supplied in a flow direction orthogonal to a generation direction of [said] laser light and across the [said] gap.

11. (Amended) The laser oscillating apparatus according to claim 8, wherein the [said] laser gas is supplied in a flow direction orthogonal to a generation direction of [said] laser light and across the [said] gap.

12. (Amended) The laser oscillating apparatus according to claim 1, wherein the [said] electromagnetic wave is a microwave.

13. (Amended) The laser oscillating apparatus according to claim 8, wherein the [said] electromagnetic wave is a microwave.

14. (Amended) The laser oscillating apparatus according to claim 1, wherein the [said] laser gas is at least one inert gas selected from Kr, Ar, Ne and He or a gaseous mixture of the [said] at least one inert gas and an F_2 gas.

15. (Amended) The laser oscillating apparatus according to claim 8, wherein the [said] laser gas is at least one inert gas selected from Kr, Ar, Ne and He or a gaseous mixture of the [said] at least one inert gas and an F_2 gas.

16. (Amended) An exposure apparatus comprising:

the laser oscillating apparatus according to claim 1, said laser oscillating apparatus being [as] a light source that emits illumination light;

a first optical unit that irradiates a reticle, where a predetermined pattern is formed, with the illumination light from said laser oscillating apparatus; and

a second optical unit that irradiates an irradiated surface with the illumination light via said reticle,

wherein the [said] predetermined pattern on said reticle is projected on the [said] irradiated surface upon exposure of the [said] irradiated surface.

17. (Amended) A device fabrication method comprising:

a step of applying a photosensitive material to an irradiated surface;

a step of exposing the [said] irradiated surface coated with the [said] photosensitive material via a predetermined pattern by using the exposure apparatus according to claim 16; and

a step of developing said photosensitive material exposed via the [said] predetermined pattern.

18. (Amended) The device fabrication method according to claim 17, wherein the [said] irradiated surface is a wafer surface, and wherein a semiconductor device is formed on the [said] wafer surface.